



ROYAL INSTITUTE  
OF TECHNOLOGY

# Semiconductor Devices

## Spring 2019

Lecture 7

# This Lecture

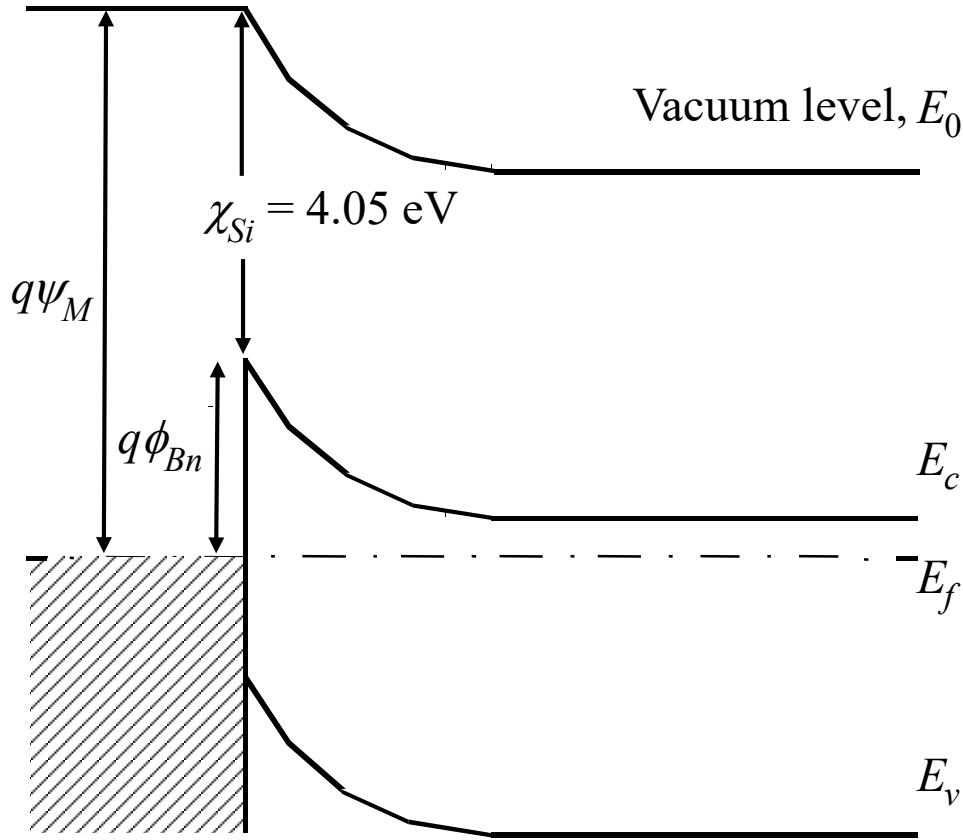
- Reading
  - Chapter 4, part III
- Concepts:
  - Metal-semiconductor contacts

# *Part III: Metal-Semiconductor Junction*

Two kinds of metal-semiconductor contacts:

- *Rectifying Schottky diodes: metal on lightly doped silicon*
- *Low-resistance ohmic contacts: metal on heavily doped silicon*

## $\phi_{Bn}$ Increases with Increasing Metal Work Function



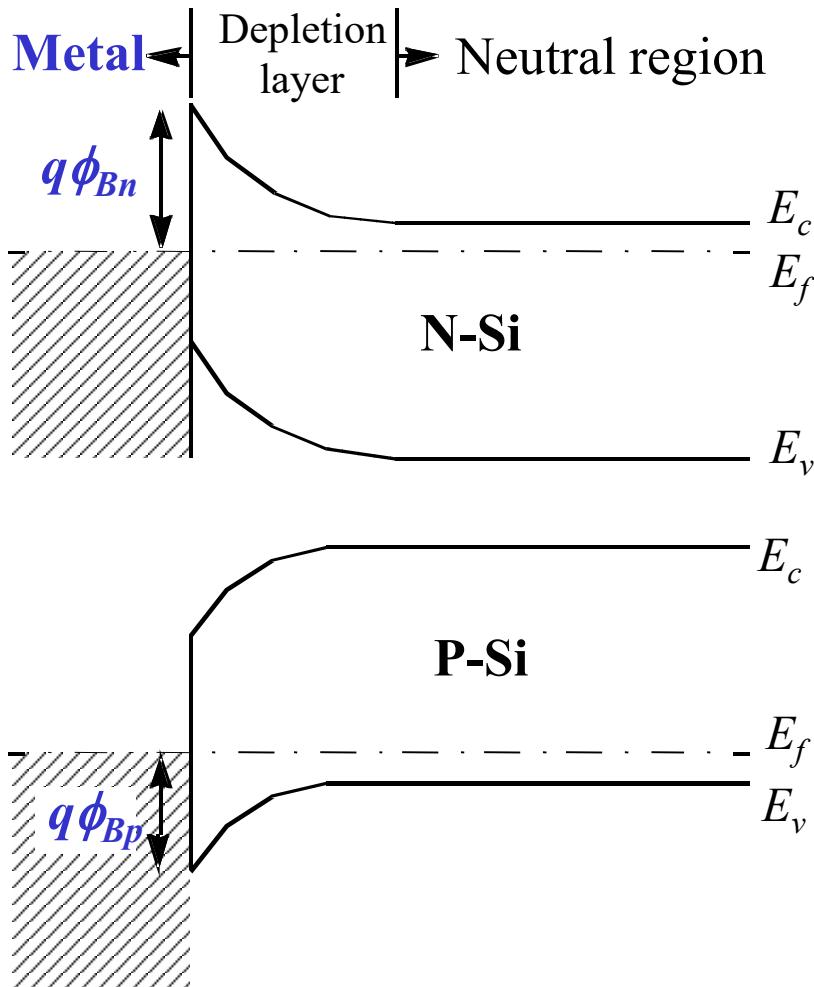
$\psi_M$  : Work Function  
of metal

$\chi_{Si}$  : Electron Affinity of Si

Theoretically,  
$$\phi_{Bn} = \psi_M - \chi_{Si}$$

## 4.16 Schottky Barriers

Energy Band Diagram of Schottky Contact



- Schottky barrier height,  $\phi_B$ , is a function of the metal material.
- $\phi_B$  is the most important parameter. The sum of  $q\phi_{Bn}$  and  $q\phi_{Bp}$  is equal to  $E_g$ .

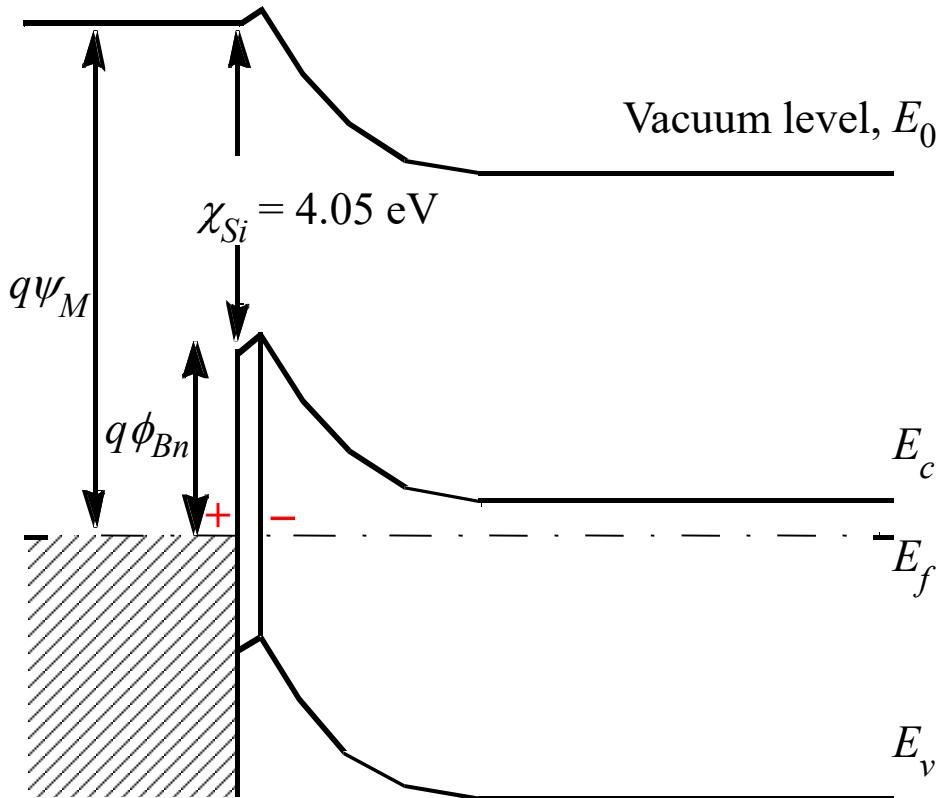
## *Schottky barrier heights for electrons and holes*

Metal	Mg	Ti	Cr	W	Mo	Pd	Au	Pt
$\phi_{Bn}$ (V)	0.4	0.5	0.61	0.67	0.68	0.77	0.8	0.9
$\phi_{Bp}$ (V)		0.61	0.5		0.42		0.3	
Work Function	3.7	4.3	4.5	4.6	4.6	5.1	5.1	5.7
$\psi_m$ (V)								

$$\phi_{Bn} + \phi_{Bp} \approx E_g$$

$\phi_{Bn}$  increases with increasing metal work function

# Fermi Level Pinning



- A high density of energy states in the bandgap at the metal-semiconductor interface pins  $E_f$  to a narrow range and  $\phi_{Bn}$  is **typically 0.4 to 0.9 V**
- **Question:** What is the typical range of  $\phi_{Bp}$ ?

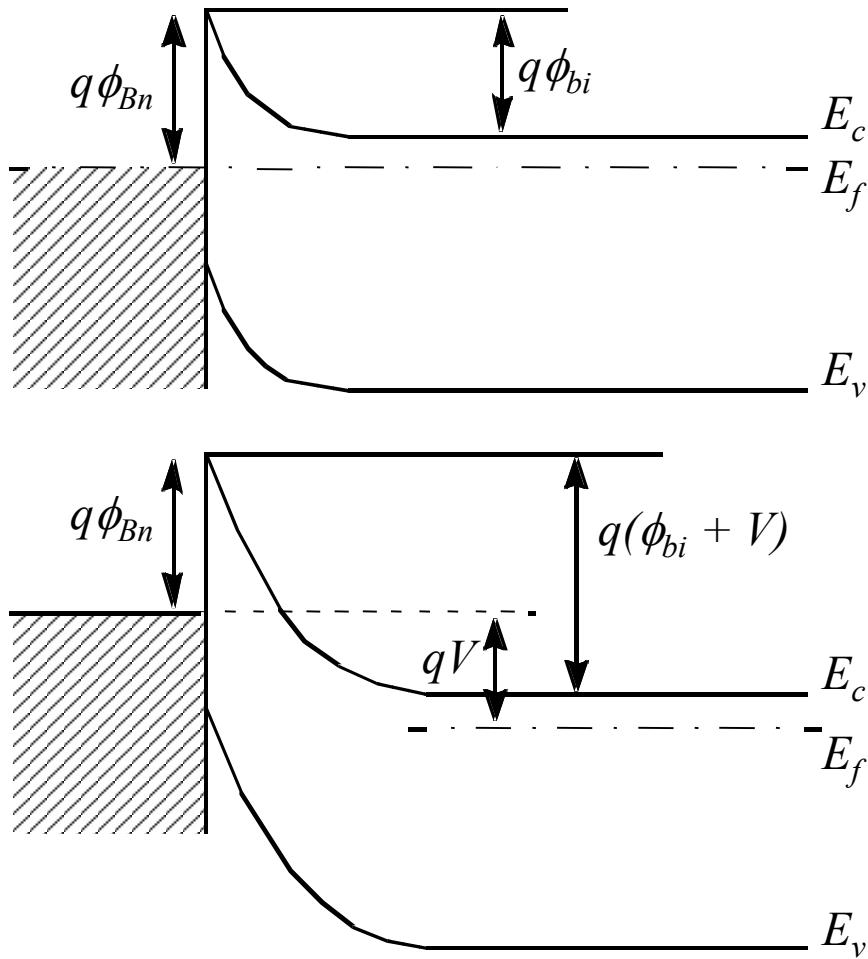
## *Schottky Contacts of Metal Silicide on Si*

**Silicide:** A silicon and metal compound. It is conductive similar to a metal.

Silicide-Si interfaces are more stable than metal-silicon interfaces. After metal is deposited on Si, an annealing step is applied to form a silicide-Si contact. The term **metal-silicon contact** includes and almost always means silicide-Si contacts.

Silicide	ErSi <sub>1.7</sub>	HfSi	MoSi <sub>2</sub>	ZrSi <sub>2</sub>	TiSi <sub>2</sub>	CoSi <sub>2</sub>	WSi <sub>2</sub>	NiSi <sub>2</sub>	Pd <sub>2</sub> Si	PtSi
$\phi_{Bn}$ (V)	0.28	0.45	0.55	0.55	0.61	0.65	0.67	0.67	0.75	0.87
$\phi_{Bp}$ (V)			0.55	0.49	0.45	0.45	0.43	0.43	0.35	0.23

# Using C-V Data to Determine $\phi_B$



$$\begin{aligned} q\phi_{bi} &= q\phi_{Bn} - (E_c - E_f) \\ &= q\phi_{Bn} - kT \ln \frac{N_c}{N_d} \end{aligned}$$

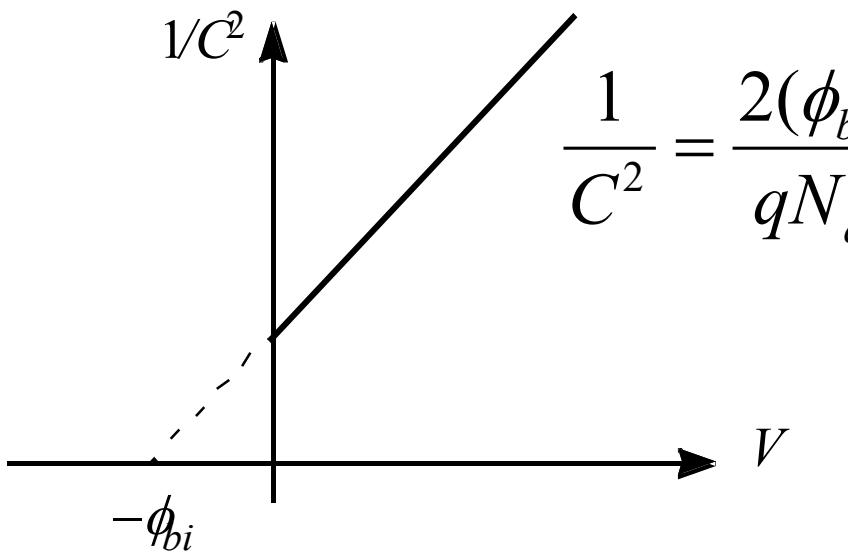
$$W_{dep} = \sqrt{\frac{2\epsilon_s(\phi_{bi} + V)}{qN_d}}$$

$$C = \frac{\epsilon_s}{W_{dep}} A$$

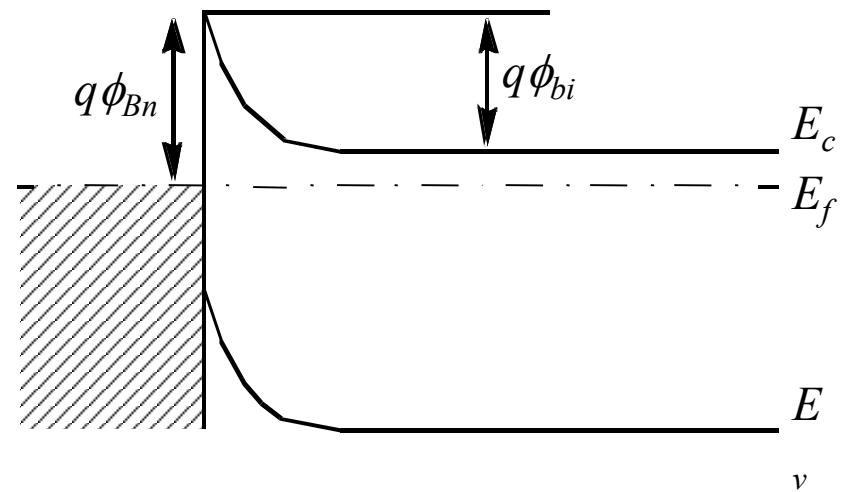
**Question:**

How should we plot the CV data to extract  $\phi_{bi}$ ?

## Using CV Data to Determine $\phi_B$



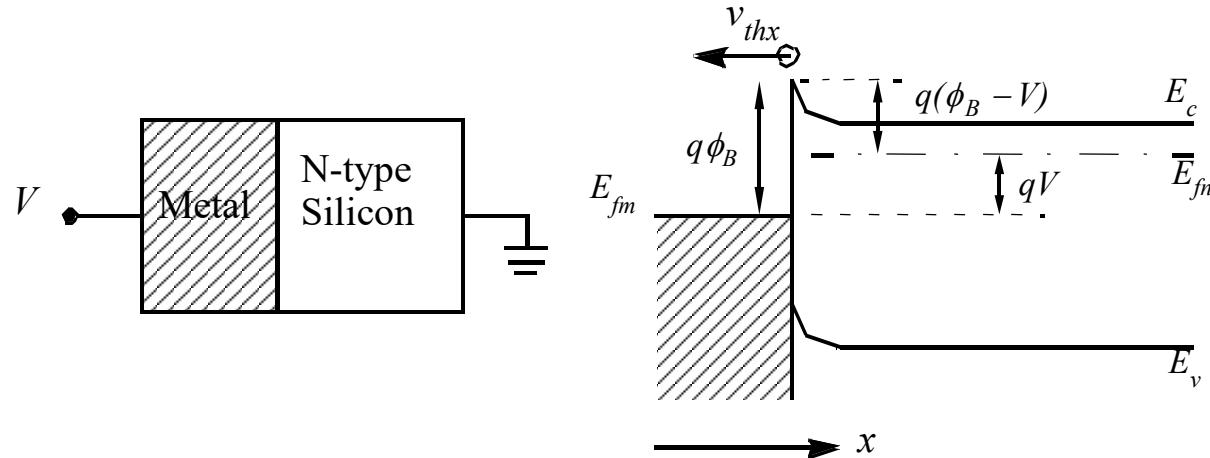
$$\frac{1}{C^2} = \frac{2(\phi_{bi} + V)}{qN_d\epsilon_s A^2}$$



Once  $\phi_{bi}$  is known,  $\phi_B$  can be determined using

$$q\phi_{bi} = q\phi_{Bn} - (E_c - E_f) = q\phi_{Bn} - kT \ln \frac{N_c}{N_d}$$

## 4.17 Thermionic Emission Theory



$$n = N_c e^{-q(\phi_B - V)/kT} = 2 \left[ \frac{2\pi m_n k T}{h^2} \right]^{3/2} e^{-q(\phi_B - V)/kT}$$

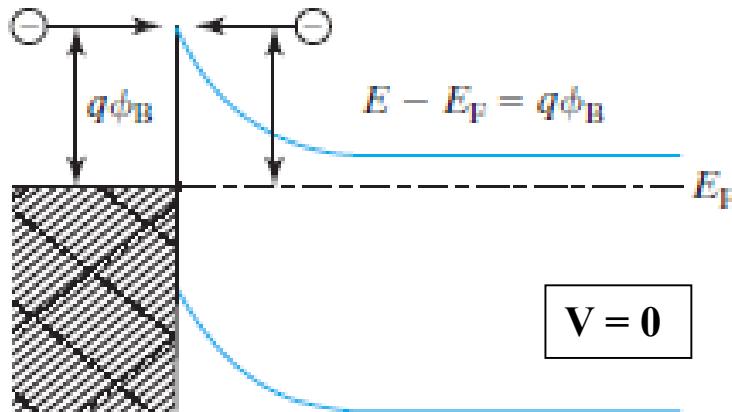
$$v_{th} = \sqrt{3kT / m_n} \quad v_{thx} = -\sqrt{2kT / \pi m_n}$$

$$J_{S \rightarrow M} = -\frac{1}{2} q n v_{thx} = \frac{4\pi q m_n k^2}{h^3} T^2 e^{-q\phi_B/kT} e^{qV/kT}$$

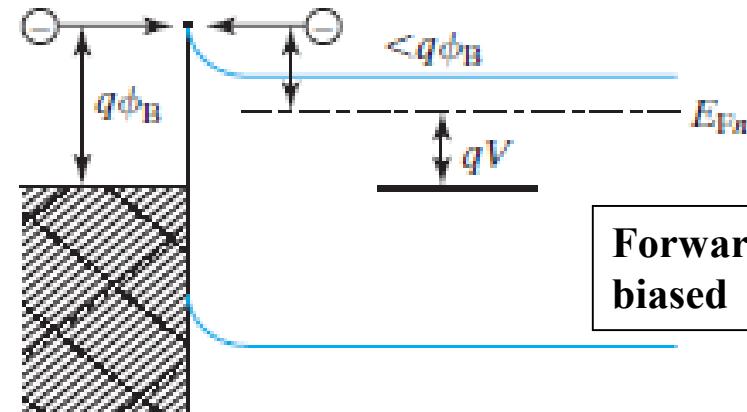
$$= J_0 e^{qV/kT}, \text{ where } J_0 \approx 100 e^{-q\phi_B/kT} \text{ A/cm}^2$$

## 4.18 Schottky Diodes

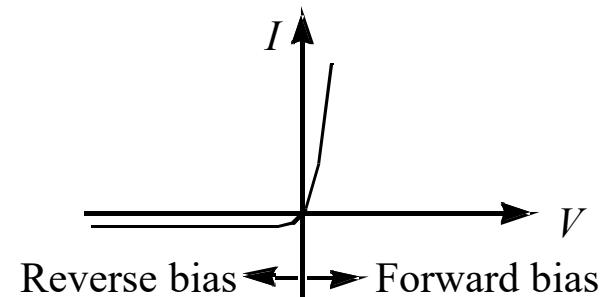
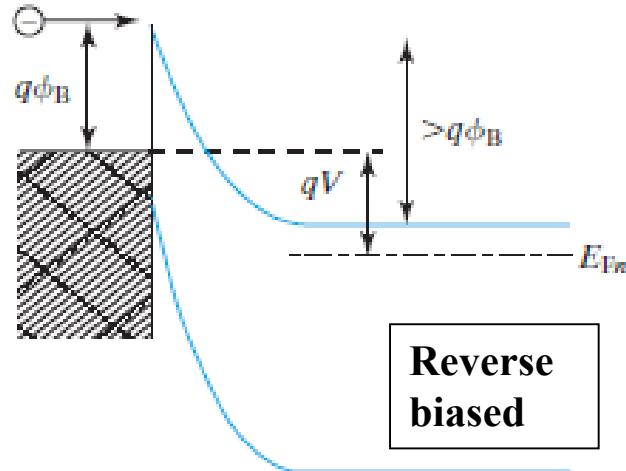
$$I_{M \rightarrow S} = -I_0 \quad I_{S \rightarrow M} = I_0$$



$$I_{M \rightarrow S} = -I_0 \quad I_{S \rightarrow M} = I_0 e^{qV/kT}$$

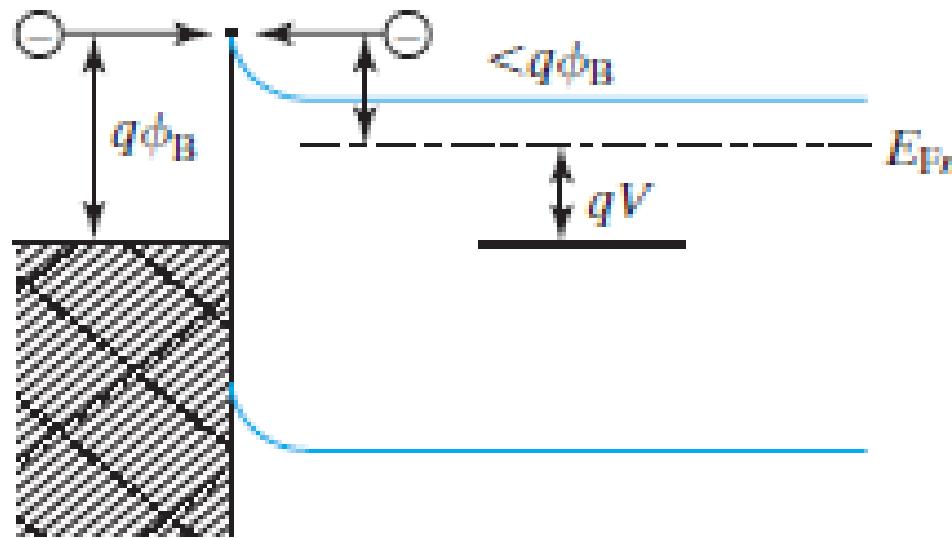


$$I_{M \rightarrow S} = -I_0 \quad I_{S \rightarrow M} \approx 0$$



## 4.18 Schottky Diodes

$$I_{M \rightarrow S} = -I_0 \quad I_{S \rightarrow M} = I_0 e^{qV/kT}$$

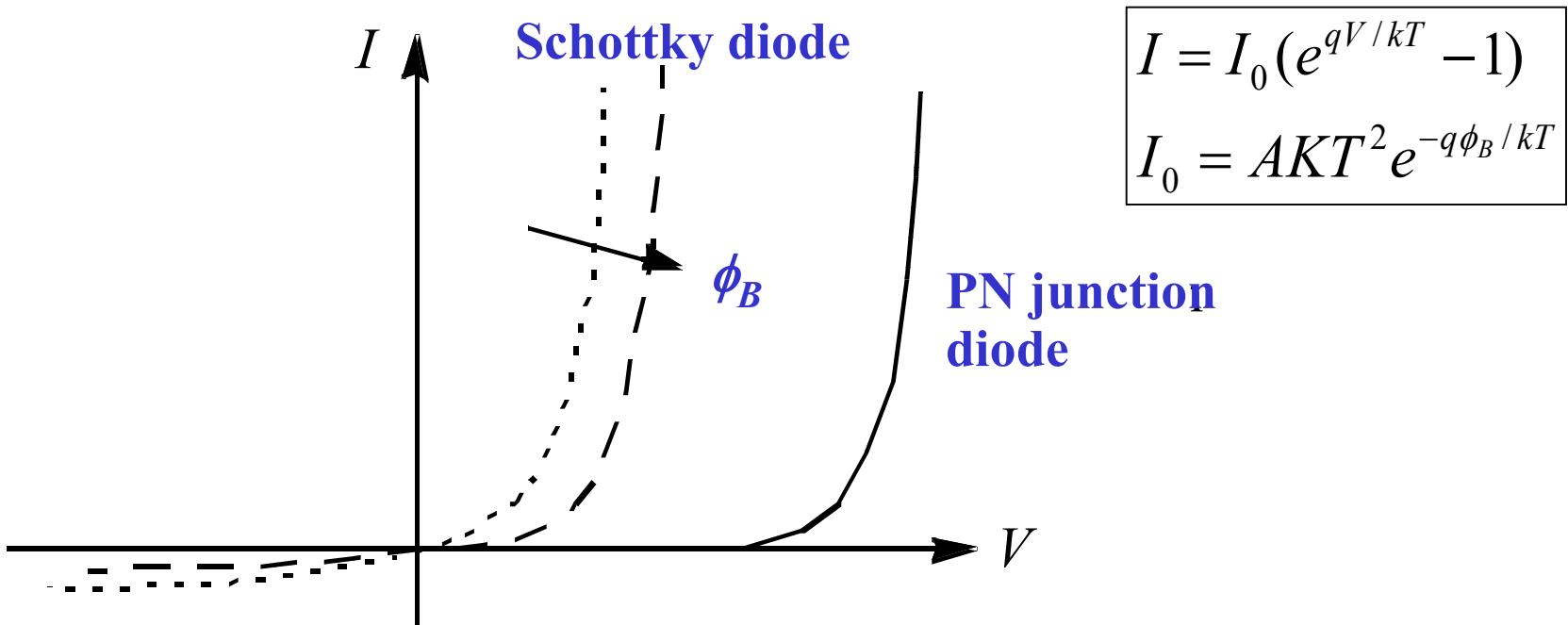


$$I_0 = A K T^2 e^{-q\phi_B/kT}$$

$$K = \frac{4\pi q m_n k^2}{h^3} \approx 100 \text{ A}/(\text{cm}^2 \cdot \text{K}^2)$$

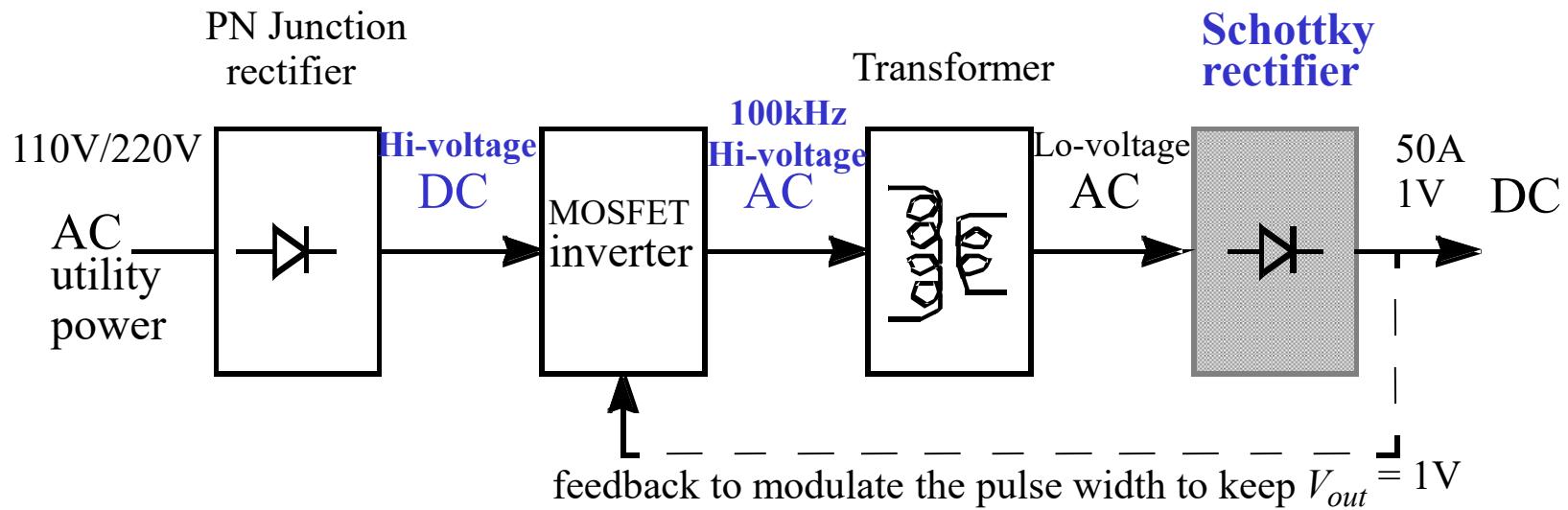
$$I = I_{S \rightarrow M} + I_{M \rightarrow S} = I_0 e^{qV/kT} - I_0 = I_0 (e^{qV/kT} - 1)$$

## 4.19 Applications of Schottky Diodes

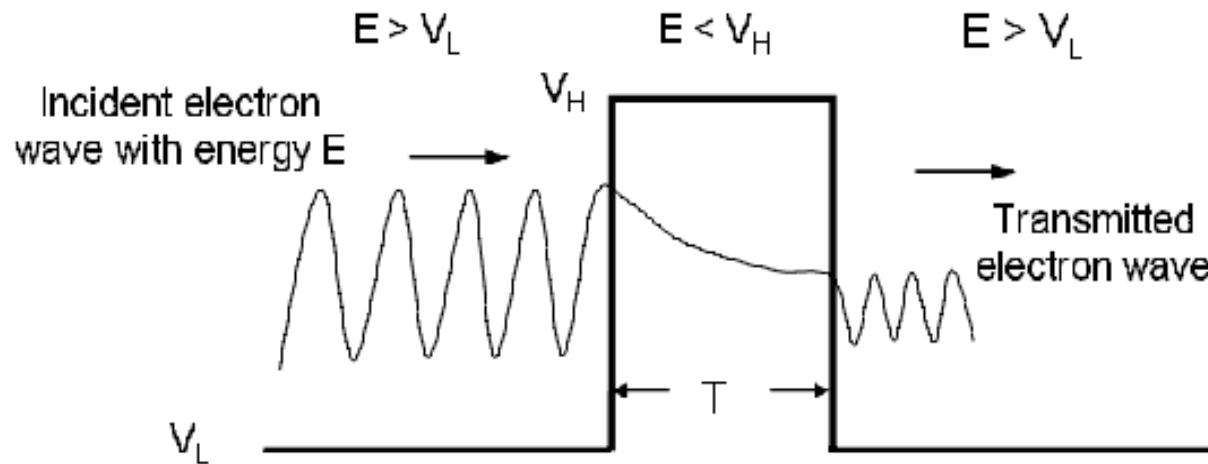


- $I_0$  of a Schottky diode is  $10^3$  to  $10^8$  times larger than a PN junction diode, depending on  $\phi_B$ . A larger  $I_0$  means a smaller forward drop  $V$ .
- A Schottky diode is the preferred rectifier in low voltage, high current applications.

# *Switching Power Supply*



## 4.20 Quantum Mechanical Tunneling



*Tunneling probability:*

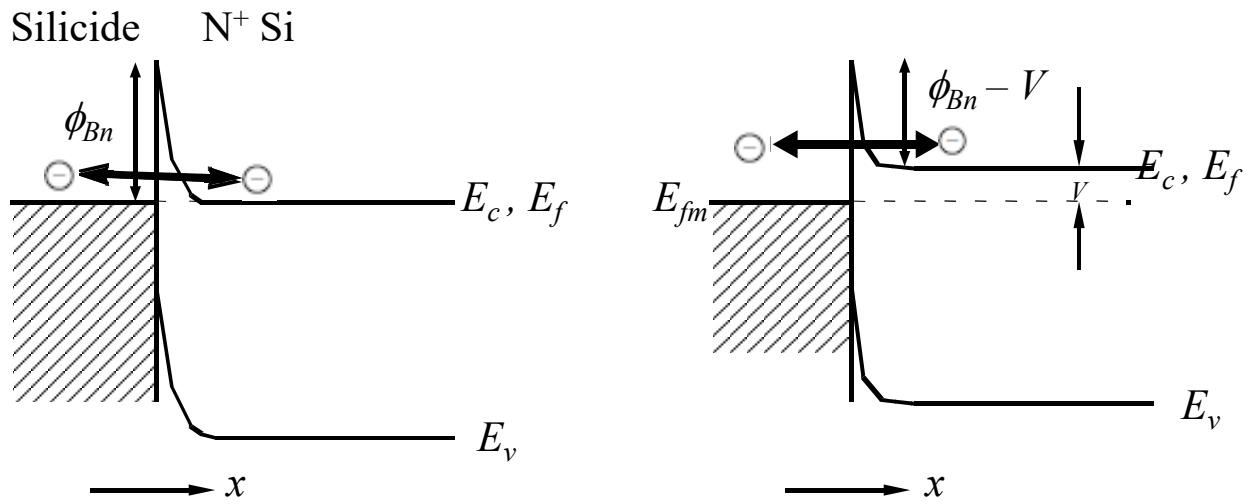
$$P \approx \exp\left(-2T \sqrt{\frac{8\pi^2 m}{h^2} (V_H - E)}\right)$$

## 4.21 Ohmic Contacts

$$W_{dep} = \sqrt{\frac{2\epsilon_s \phi_{Bn}}{qN_d}}$$

Tunneling probability:

$$P \approx e^{-H\phi_{Bn}/\sqrt{N_d}}$$

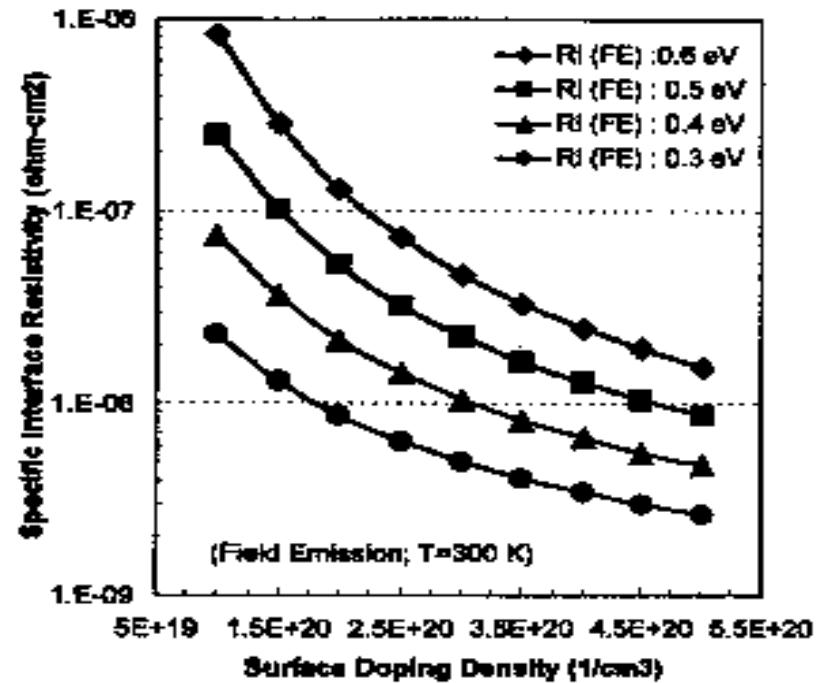
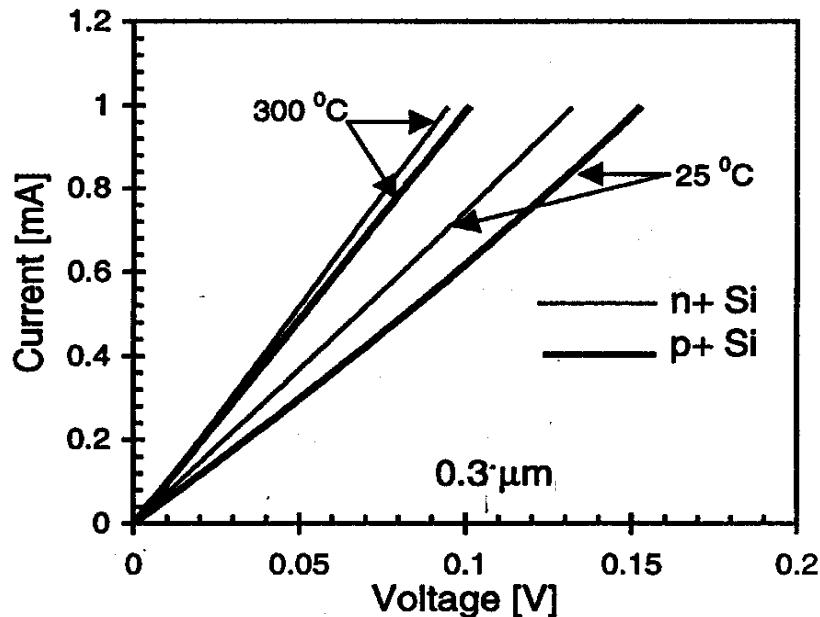


$$T \approx W_{dep} / 2 = \sqrt{\epsilon_s \phi_{Bn} / 2qN_d}$$

$$H = \frac{4\pi}{h} \sqrt{\epsilon_s m_n / q}$$

$$J_{S \rightarrow M} \approx \frac{1}{2} qN_d v_{thx} P = qN_d \sqrt{kT / 2\pi m_n} e^{-H(\phi_{Bn} - V) / \sqrt{N_d}}$$

## 4.21 Ohmic Contacts



$$R_c \equiv \left( \frac{dJ_{S \rightarrow M}}{dV} \right)^{-1} = \frac{2e^{H\phi_{Bn}/\sqrt{N_d}}}{qv_{thx} H \sqrt{N_d}} \propto e^{H\phi_{Bn}/\sqrt{N_d}} \Omega \cdot \text{cm}^2$$

## 4.22 Chapter Summary

### Part I: PN Junction

$$\phi_{bi} = \frac{kT}{q} \ln \frac{N_d N_a}{n_i^2}$$

The potential barrier increases by 1 V if a 1 V reverse bias is applied

depletion width

$$W_{dep} = \sqrt{\frac{2\epsilon_s \cdot \text{potential barrier}}{qN}}$$

junction capacitance

$$C_{dep} = A \frac{\epsilon_s}{W_{dep}}$$

## ***4.22 Chapter Summary***

- Under forward bias, minority carriers are injected across the junction.
- The quasi-equilibrium boundary condition of minority carrier densities is:

$$n(x_p) = n_{P0} e^{qV/kT}$$

$$p(x_N) = p_{N0} e^{qV/kT}$$

- Most of the minority carriers are injected into the more lightly doped side.

## 4.22 Chapter Summary

- Steady-state continuity equation:

$$\frac{d^2 p'}{dx^2} = \frac{p'}{D_p \tau_p} = \frac{p'}{L_p^2}$$

$$L_p \equiv \sqrt{D_p \tau_p}$$

- Minority carriers diffuse outward  $\propto e^{-|x|/L_p}$  and  $e^{-|x|/L_n}$
- $L_p$  and  $L_n$  are the diffusion lengths

$$I = I_0(e^{qV/kT} - 1)$$

$$I_0 = A q n_i^2 \left( \frac{D_p}{L_p N_d} + \frac{D_n}{L_n N_a} \right)$$

## **4.22 Chapter Summary**

### ***Part II: Optoelectronic Applications***

$$\text{Solar cell power} = I_{sc} \times V_{oc} \times FF$$

- ~100um Si or <1um direct-gap semiconductor can absorb most of solar photons with energy larger than  $E_g$ .
- Carriers generated within diffusion length from the junction can be collected and contribute to the Short Circuit Current  $I_{sc}$ .
- Theoretically, the highest efficiency (~24%) can be obtained with 1.9eV  $>E_g>1.2\text{eV}$ . Larger  $E_g$  lead to too low  $I_{sc}$  (low light absorption); smaller  $E_g$  leads to too low Open Circuit Voltage  $V_{oc}$ .

## ***4.22 Chapter Summary***

### ***LED and Solid-State Lighting***

- Electron-hole recombination in direct-gap semiconductors such as GaAs produce light.
- Ternary semiconductors such as GaAsP provide tunable  $E_g$  and LED color.
- Quaternary semiconductors such as AlInGaP provide tunable  $E_g$  and lattice constants for high quality epitaxial growth on inexpensive substrates.
- White light can be obtained with UV LED and wavelength conversion
- Organic semiconductor is an important low-cost LED material class. Used in OLED displays both for [iPhones](#) and [other brands](#)

## 4.22 Chapter Summary

### Part III: Metal-Semiconductor Junction

$$I_0 = AKT^2 e^{-q\phi_B/kT}$$

- Schottky diodes have large reverse saturation current, determined by the Schottky barrier height  $\phi_B$ , and therefore lower forward voltage at a given current density.
- Ohmic contacts relies on tunneling. Low resistance contact requires low  $\phi_B$  and higher doping concentration.

$$R_c \propto e^{-(\frac{4\pi}{h}\phi_B \sqrt{\epsilon_s m_n / qN_d})} \Omega \cdot \text{cm}^2$$

## $\phi_{Bn}$ Increases with Increasing Metal Work Function

